

# Jan van den Hurk

## List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/1298029/publications.pdf>

Version: 2024-02-01

12  
papers

995  
citations

1039406

9  
h-index

1281420

11  
g-index

14  
all docs

14  
docs citations

14  
times ranked

1530  
citing authors

#	ARTICLE	IF	CITATIONS
1	Nanobatteries in redox-based resistive switches require extension of memristor theory. Nature Communications, 2013, 4, 1771.	5.8	473
2	Redox Reactions at Cu,Ag/Ta <sub>2</sub> O <sub>5</sub> Interfaces and the Effects of Ta <sub>2</sub> O <sub>5</sub> Film Density on the Forming Process in Atomic Switch Structures. Advanced Functional Materials, 2015, 25, 6374-6381.	7.8	148
3	Realization of Boolean Logic Functionality Using Redox-Based Memristive Devices. Advanced Functional Materials, 2015, 25, 6414-6423.	7.8	127
4	Volatile resistance states in electrochemical metallization cells enabling non-destructive readout of complementary resistive switches. Nanotechnology, 2014, 25, 425202.	1.3	64
5	Ag/GeS <sub>x</sub> /Pt-based complementary resistive switches for hybrid CMOS/Nanoelectronic logic and memory architectures. Scientific Reports, 2013, 3, 2856.	1.6	44
6	Direct Observation of Charge Transfer in Solid Electrolyte for Electrochemical Metallization Memory. Advanced Materials, 2012, 24, 4552-4556.	11.1	42
7	Physical origins and suppression of Ag dissolution in GeS <sub>x</sub> -based ECM cells. Physical Chemistry Chemical Physics, 2014, 16, 18217.	1.3	30
8	Preparation and characterization of GeS <sub>x</sub> thin-films for resistive switching memories. Thin Solid Films, 2013, 527, 299-302.	0.8	22
9	Processes and Limitations during Filament Formation and Dissolution in GeS <sub>x</sub> -based ReRAM Memory Cells. Journal of Physical Chemistry C, 2015, 119, 18678-18685.	1.5	20
10	Simulation of polarity independent RESET in electrochemical metallization memory cells. , 2013, , .		13
11	(Keynote) Atomic Scale and Interface Interactions in Redox-Based Resistive Switching Memories. ECS Transactions, 2014, 64, 3-18.	0.3	8
12	A compact and low-weight sputtering unit for in situ investigations of thin film growth at synchrotron radiation beamlines. Review of Scientific Instruments, 2015, 86, 053906.	0.6	4